



#11/C1765  
PATENT  
3/16/03

Customer No. 22,852  
Attorney Docket No. 07553.0009

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: )  
Michiaki SANO ) Group Art Unit: 1765  
Serial No.: 09/671,201 ) Examiner: L. Vinh  
Filed: September 28, 2000 )  
For: PLASMA PROCESSING )  
METHOD )

Assistant Commissioner for Patents  
Washington, DC 20231

Sir:

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**AMENDMENT**

In reply to the Office Action dated October 3, 2002, the period for reply having been extended for one month by a request for extension and fee payment filed concurrently herewith, please amend the application as follows:

**IN THE CLAIMS:**

Please cancel claims 10-28 and 38-40 without prejudice or disclaimer, amend claim 32, and add new claims 41-62, as follows:

32. (Amended) A plasma processing method comprising:
- etching a film by utilizing a resist film as a mask;
  - ashing the film with a first high-frequency biasing power level substantially halfway through the resist film, after etching; and

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